Docket No.: SHIGA7.033APC Customer No. 20,995

INFORMATION DISCLOSURE STATEMENT

Applicant : Hada et al.

App. No : 10/557,694

Filed: November 22, 2005

For : RESIN FOR PHOTORESIST

COMPOSITION, PHOTORESIST

COMPOSITION AND METHOD FOR

FORMING RESIST PATTERN

Examiner : Anca Eoff

Art Unit : 1795

Mail Stop Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 17 (seventeen) references to be considered by the Examiner. Also enclosed are 10 (ten) foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

This Information Disclosure Statement is being filed before the mailing date of a final action and before the mailing of a Notice of Allowance. This Statement is accompanied by the fees set forth in 37 C.F.R. § 1.17(p). The Commissioner is hereby authorized to charge any additional fees which may be required or to credit any overpayment to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

CERTIFICATE OF EES WEB.

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Agent of Record Customer No. 20,995 (619) 235-8550

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